

IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claim 1 (currently amended): A film treatment apparatus, ~~wherein a film of a coating solution coated on a substrate is gelatinized by using at least a second gas including a prescribed concentration of a vapor of prescribed solvent and a first gas, which comprises~~ comprising:

a chamber ~~for placing said~~ configured to receive a substrate coated pre-coated with ~~[[said]] a film of a coating solution;~~

a first mass flow controller ~~for supplying~~ configured to supply said chamber with ~~[[said]] a first gas including an ammonia gas; and~~

a second mass flow controller ~~for supplying~~ configured to supply said chamber with ~~[[said]] a second gas, said second gas including one of a nitrogen gas and air including a prescribed amount of a water vapor,~~

wherein said film of the coating solution is gelatinized by using said first and second gas.

Claim 2 (currently amended): The film treatment apparatus according to claim 1, ~~[[which]] further comprises~~ comprising:

an exhaust means for exhausting mechanism configured to exhaust said chamber; and
a chamber pressure control mechanism ~~for detecting~~ configured to detect a pressure in said chamber, ~~operating and to operate~~ said exhaust ~~means and controlling mechanism to control~~ said pressure.

Claim 3 (currently amended): The film treatment apparatus according to claim 1,
[[which]] further ~~comprises~~ comprising:

a concentration sensor ~~for measuring~~ configured to measure a concentration of said first gas in said chamber;

a pressure sensor ~~for measuring~~ configured to measure a pressure in said chamber;

an exhaust ~~means for exhausting~~ mechanism configured to exhaust said chamber;

a chamber pressure control mechanism ~~for operating~~ configured to operate said exhaust [[means]] mechanism on the basis of a measurement signal from said pressure sensor ~~and for controlling~~ to control said pressure; and

a gas composition control mechanism ~~for controlling~~ configured to control said first or second mass flow controller on the basis of a measurement signal from said concentration sensor thereby keeping constant said concentration of said first gas.

Claim 4 (currently amended): The film treatment apparatus according to claim 3,
[[which]] further ~~comprises~~ comprising:

a coating unit ~~for coating~~ configured to coat a coating solution on a substrate and ~~forming~~ to form a film on said substrate.

Claim 5 (canceled)

Claim 6 (currently amended): The film treatment apparatus according to claim 1,
[[which]] further ~~comprises~~ comprising:

a mixer ~~for mixing~~ configured to mix said first and second gases, ~~wherein and to~~ supply the mixed gas ~~from said mixer is supplied~~ into said chamber.

Claim 7 (currently amended): The film treatment apparatus according to claim 3, wherein said exhaust mechanism includes an exhaust valve and said chamber pressure control mechanism controls said pressure by controlling a throttle of ~~[[an]]~~ said exhaust valve of said exhaust mechanism on the basis of a measurement signal from said pressure sensor.

Claim 8 (withdrawn): A film treatment method for gelatinizing a film of a coating solution coated on a substrate by using at least a second gas including a prescribed concentration of a vapor of prescribed solvent and a first gas, which comprises the steps of:

- a first step for forming said film of a coating solution on said substrate;
- a second step for transporting said substrate with said film into a treatment chamber;

and

- a third step for treating said film by supplying said treatment chamber with said first and second gases each of which flow is controlled by a respective mass flow controller.

Claim 9 (withdrawn): A film treatment method for gelatinizing a film of a coating solution coated on a substrate by using at least a second gas including a prescribed concentration of a vapor of prescribed solvent and a first gas, which comprises the steps of:

- a first step for forming said film of a coating solution on said substrate in an atmosphere of said second gas;
- a second step for transporting said substrate with said film into a treatment chamber;

and

- a third step for treating said film by supplying said treatment chamber with said first gas through a mass flow controller and supplying said treatment chamber with said second gas.

Claim 10 (new): A film treatment apparatus, comprising:

means for receiving a substrate pre-coated with a film of a coating solution;

first means for supplying said means for receiving with a first gas including an ammonia gas; and

second means for supplying said means for receiving with a second gas, said second gas including one of a nitrogen gas and air including a prescribed amount of a water vapor,

wherein said film of the coating solution is gelatinized by using said first and second gas.